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(54) **LIGHT-TRANSMITTING FILM AND SPUTTERING
TARGET FOR FORMING THE SAME**

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a sputtering target for producing an optical disk-protective film of low reflectivity with high light transmittance through diminishing particle generation during sputtering operation, thereby reducing the frequency of suspending or stopping the sputtering operation to effect raising film production efficiency.

SOLUTION: This sputtering target for forming light-transmitting film is composed of 0.01-10 wt.% of glass-forming oxides consisting of Nb₂O₅, V₂O₅, B₂O₃, SiO₂ and P₂O₅, 0.01-20 wt.% of Al₂O₃+Ga₂O₃, and, as necessary, 0.01-5 wt.% of ZrO₂ and/or TiO₂ as rigid material oxide (s), and the rest of at least one kind of oxide selected from In₂O₃, SnO₂ and ZnO.

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